

# CHROMIUM OXIDE

Sputtering Target

**NS6130-10 -1441**

## Quick Facts

Product	:	Chromium Oxide Sputtering Target
Stock No	:	NS6130-10 -1441
CAS	:	1308-38-9
Molecular Formula	:	Cr <sub>2</sub> O <sub>3</sub>
Form	:	Solid

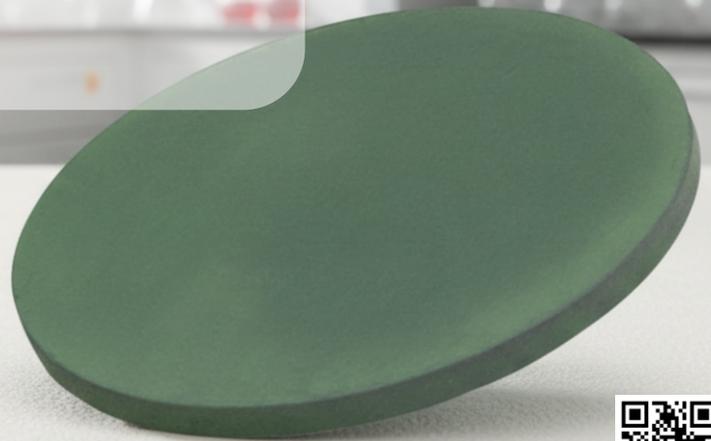
## Technical Specification

Molecular Weight	Diameter	Thickness	Purity
151.99g/mol	50.8 mm ± 1mm	3 mm ± 0.5mm	99.99%

Chromium oxide (Cr<sub>2</sub> O<sub>3</sub> ) sputtering targets are used in PVD processes to create thin films with specific properties. They are employed in thin film deposition for electronic, optical, and protective applications. Cr<sub>2</sub> O<sub>3</sub> targets produce hard, wear-resistant coatings, optical coatings for lenses and mirrors, corrosion-resistant finishes, and decorative coatings that offer both aesthetic and protective qualities.

### Applications:

- Thin Film Deposition
- Hard coating
- Optical coating
- Corrosion resistance
- Decorative finishes



\* This image is for graphic purposes only and does not represent the actual product.

